

| L Number | Hits | Search Text | DB | Time stamp |
|-------------|---------|---|---|---------------------|
| - | 2 | ("6215595").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/03 15:37 |
| - | 64 | ("3667832" "4733944" "4943733" "5097291" "5263250" "5414559" "5561081" "5657138" "5721416" "5756364" "5815494" "5854803" "5858822" "5893990" "5897799" "5900980" "5907770" "5923966" "5959779" "6104535" "6137633").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 13:47 |
| - | 14653 | excimer adj laser | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 14:33 |
| - | 2078666 | beam near\$4 (homogeneity or homogeneous or homogenizer) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 13:53 |
| - | 9238 | (excimer adj laser) and (beam near\$4 (homogeneity or homogeneous or homogenizer)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 13:53 |
| - | 33846 | ((thin adj film adj transistor) or (tft)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 13:55 |
| - | 848 | ((excimer adj laser) and (beam near\$4 (homogeneity or homogeneous or homogenizer))) and (((thin adj film adj transistor) or (tft))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 13:55 |
| - | 118 | pulsed adj laser and (((excimer adj laser) and (beam near\$4 (homogeneity or homogeneous or homogenizer))) and (((thin adj film adj transistor) or (tft)))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 13:15 |
| - | 282 | (438/149).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 14:32 |
| - | 103 | laser and (("438/149").CCLS.) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 14:35 |
| - | 79 | pulsed adj laser and (((excimer adj laser) and (beam near\$4 (homogeneity or homogeneous or homogenizer))) and (((thin adj film adj transistor) or (tft)))) and glass adj substrate | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 14:39 |
| - | 49 | (438/150).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 14:39 |
| - | 377 | (438/151).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 14:40 |

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| - | 161 | (438/152).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 14:40 |
| - | 105 | (438/153).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 14:41 |
| - | 479 | (438/164).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 14:42 |
| - | 53 | glass adj substrate and laser and (("438/164").CCLS.) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 15:41 |
| - | 3 | ("5858473").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/26 15:42 |
| - | 1274 | ion adj doping | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 12:44 |
| - | 56160 | glass adj substrate | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 12:44 |
| - | 544 | (ion adj doping) and (glass adj substrate) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 12:45 |
| - | 19765 | tft | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 12:45 |
| - | 458 | ((ion adj doping) and (glass adj substrate)) and tft | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 12:45 |
| - | 1274 | ion adj doping | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 13:14 |
| - | 290 | pulsed adj excimer adj laser | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 13:15 |
| - | 1 | "US 6215595 B1".DID. and ("US 6215595 B1".DID. and ("6215595").PN.)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 13:15 |
| - | 875 | (homogeneity or homogeneous or homogenizer) and ((thin adj film adj transistor) or tft) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 13:17 |

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| - | 0 | (ion adj doping) and (pulsed adj excimer adj laser) and ("US 6215595 B1".DID. and ("US 6215595 B1".DID. and ("6215595").PN.)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 13:17 |
| - | 6 | (ion adj doping) and (pulsed adj excimer adj laser) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 13:21 |
| - | 1 | (pulsed adj excimer adj laser) and ((ion adj doping) and ((homogeneity or homogeneous or homogenizer) and ((thin adj film adj transistor) or tft))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 13:21 |
| - | 54 | (ion adj doping) and ((homogeneity or homogeneous or homogenizer) and ((thin adj film adj transistor) or tft)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 13:25 |
| - | 1 | (ion adj doping) and (pulsed adj excimer adj laser) and ((homogeneity or homogeneous or homogenizer) and ((thin adj film adj transistor) or tft)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 13:26 |
| - | 2 | ("5958800").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 16:16 |
| - | 24480 | silicon and germanium | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 18:28 |
| - | 1274 | ion adj doping | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 18:28 |
| - | 109 | (silicon and germanium) and (ion adj doping) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 18:28 |
| - | 3 | ("5180690").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2001/09/27 19:09 |
| - | 661 | "piii" or plasma adj immersion adj ion adj implantation | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 13:24 |
| - | 577793 | laser | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 13:25 |
| - | 110 | ("piii" or plasma adj immersion adj ion adj implantation) and laser | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 13:29 |
| - | 835 | glass adj substrate and ion adj doping | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 13:30 |

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| - | 737 | laser and (glass adj substrate and ion adj doping) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 13:31 |
| - | 1150067 | semiconductor | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 13:34 |
| - | 712 | ((laser and (glass adj substrate and ion adj doping)) and semiconductor | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 16:57 |
| - | 214 | ((laser and (glass adj substrate and ion adj doping)) and semiconductor and germanium | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 17:01 |
| - | 162 | ((laser and (glass adj substrate and ion adj doping)) and semiconductor and cmos and germanium | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 17:06 |
| - | 448 | ((laser and (glass adj substrate and ion adj doping)) and semiconductor and cmos | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 17:09 |
| - | 11 | ((("5699191") or ("5986807") or ("6061375") or ("6212012") or ("6300176")).PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2002/06/20 18:40 |
| - | 9568 | moving near substrate | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/02 14:24 |
| - | 161 | laser adj annealing and (moving near substrate) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/02 14:25 |
| - | 135 | glass adj substrate and (laser adj annealing and (moving near substrate)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/02 15:08 |
| - | 321 | laser and divergence and convergence and (inspection or monitoring) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/02 15:09 |
| - | 58 | substrate and defects and surface and (laser and divergence and convergence and (inspection or monitoring)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/02 15:13 |
| - | 52 | ((annular or circle or circular or round) and (substrate and defects and surface and (laser and divergence and convergence and (inspection or monitoring))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/02 15:14 |
| - | 585 | ((438/164).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/09/03 15:58 |

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| - | 644 | (438/166).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB | 2003/09/03 15:58 |
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